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	Filing Date	Even Date Herewith 2/27/04		
	First Named Inventor	Forbes, Leonard		
	Group Art Unit	Unknown 28/8		
	Examiner Name	Unknown PHAN		
Sheet 1 of 8	Attorney Docket No: 1	1303.058US2		

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	Examiner Name	Unknown PHAN			
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	First Named Inventor	Forbes, Leonard			
	Group Art Unit	Unknown 28/8			
	Examiner Name	Unknown PHAN			
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	First Named Inventor	Forbes, Leonard			
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT	Application Number	Unknown 10/789,041	
(Use as many sheets as necessary)	Filing Date	Even Date Herewith 2/27/04 Forbes, Leonard	
	First Named Inventor		
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